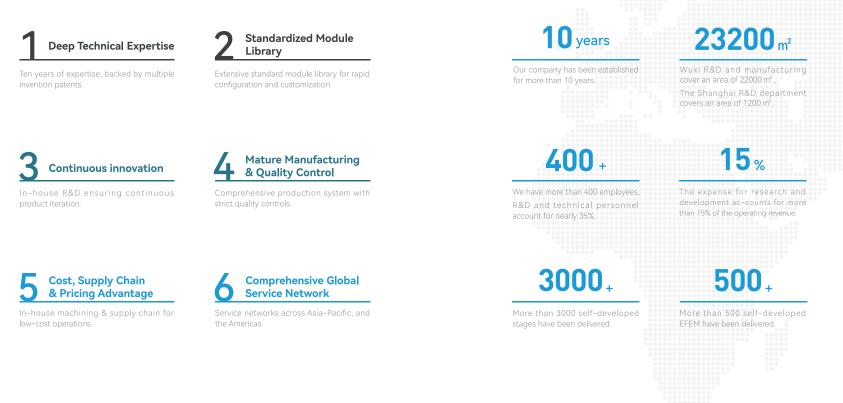


XIVI's Advantages



XIVI's Data items

ABOUT XIVI

With nearly 10 years of experience in precision motion control research and development, xivi has gathered expertise in the precision manufacturing industry to form the development strategy of "Ultra-precision Positioning, Transmission and Storage Solution Manufacturer".

Pursuing micron and nanometer precision motion control technology, practicing precision manufacturing capabilities and excellent production management, we are committed to providing innovative industrial products for the industrial automation market.

Semiconductor Automation Solutions



EFEM



Equipped with direct-drive servo motors, clean Robot, Aligner, and linear Track to achieve high throughput for 6', 8', and 12' wafers. SEMI standard FOUP, FOSB, Open Cassette, SMIF Port and other loading units can be matched according to different needs, and mix and match of loading units is also possible.

Feature

- High throughput can be achieved with the optional 2 Aligners.
- Compatible with 150/200/300mm Wafer.
- Vacuum pick-and-place and edge-grip pick-and-place (optional).
- > OHT, AGV can correspond.

Optional

- E84
 OCR
 Lonizer
 Teaching pendant
 Chemical Filter
 Autoteaching
- Compatible with Barcode Reader and RF-ID Reader.

Specifications

Model Number	VEM2200	VEM2300	VEM2400		
Number of Ports	2	3	4		
Target of transmission		300mm Wafer Ø300±0.2m	m		
<u></u>	300mm FOUP 25 segments(SEMI E47.1)				
Carriers –	300mm FOSB 25 segments(SEMI E31)				
Power Supply	Single-pha	ase AC200V~AC220V±10%5	50/60Hz±5%		
Electric current	41	VA(20A/200VAC) include F	FU		
Vacuum (pressure)	/ / /	-80kPa ~ -90kPa			
Vacuum (flow)	40L/min	50L/min	60L/min		
Positive pressure (pressure)		0.6MPa ~ 0.7MPa			
Positive pressure (flow)	20L/min	30L/min	40L/min		

SORTER

Feature

- Compatible with 200mm/300mm Wafer
- Multiple pick & place options
- Reads IDs from top and bottom of wafer.
- > OHT, AGV can be corresponded
- Optional edge detection function



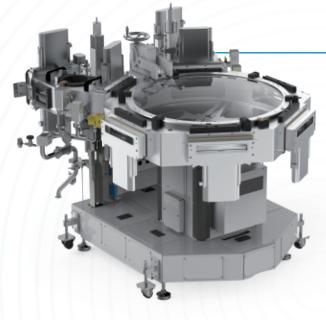
Specifications

Model number	SW2200	SW2300	SW2400		
Number of Ports	2	3	4		
Target of Transmission	300mm Wafer Ø300±0.2mm				
Carriers —	:	300mm FOUP 25(SEMI E4	7.1)		
Camera	300mm FOSB 25(SEMI M31)				
Power Supply	Single-ph	ase AC200V~AC220V±109	%50/60Hz±5%		
Electric Current	4kVA(20A/200VAC) include FFU				
Vacuum (pressure)		-80kPa ~ -90kPa			
Vacuum (flow)	40l/min	50L/min	60L/min		
Positive Pressure (pressure)		0.6MPa ~ 0.7MPa			
Positive Pressure (flow)	20L/min	30L/min	40L/min		

High throughput is achieved by adopting a clean robot and Aligner with direct-drive servo motors. Loadport can add various units to the front, back, and sides of the frame, and can be directly interfaced with OHT and AGV.

VTM / AMR

VTM



Vacuum Transfer Module (VTM) is an efficient transfer equipment based on the principle of negative vacuum pressure, which consists of vacuum generator, transfer pipeline, carrying device and control system, and drives the material along the pipeline through the pressure difference. It has the advantages of high efficiency and fast transmission, avoiding material contamination from the outside world, smooth operation, low noise, small footprint, etc. It can be flexibly adapted to automated production lines.

AMR

AMR (Autonomous Mobile Robot) is based on artificial intelligence and autonomous navigation technology, real-time perception of the environment through LIDAR, vision sensors, SLAM (real-time localization and map construction) technology, autonomous planning of the optimal path for high-precision, high-cleanliness scenarios of the wafer box automated handling, to meet the stringent requirements of the clean room, to help semiconductor production lines to achieve the core objective of zero pollution, zero error. Help semiconductor production lines to realize the core objectives of zero pollution and zero error in material transfer.



Robot ZTR-W

XIVI's vacuum manipulators have a full link arm mechanism for higher positioning accuracy. Adopting full closed-loop control and equipped with vacuum direct-drive motors, it has higher rotary accuracy and faster response time. The bidirectional dual-arm configuration allows for longer transfer distances than conventional models without enlarging the chamber, and has higher work efficiency in the face of multiple work stations.

Specifications

	Specific	ations
W	afer Size	6" / 8" / 12"
	Lifting Stroke (Z-axis)	70 mm / 125 mm
Motion Range	Rotary Stroke (T-axis)	360°(Unlimited rotation)
-	Telescopic Stroke (R-axis)	1050 mm(Depending on the fork change)
	Z-axis	±0.05 mm
Repeat Positioning	T-axis	±0.006°
Accuracy	R-axis	±0.05 mm
Body Weight		38 kg
Vacu	um Resistance	1×10 ⁻⁶ Pa
Le	akage Rate	<1×10 ⁹ std·cc/sec He
Cleanliness Level		ISO Class 1
Communication Protocols		TCP / IP
	Optional	AWC (Wafer position correction)



Robot VTR



The Atmospheric Wafer Transfer Robot (hereinafter referred to as the 'Robot') is suitable for use in atmospheric clean room environments, and consists of a body, an arm, and End effector(optional), and realises wafer transfer functions by means of suction, gripping, etc., and cyclic movements of each joint. The motion of the robot is divided into lifting motion (Z-axis), rotary motion (T-axis), and arm extension/retraction motion (R/W-axis).

Naming Convention

VTR	- 00	- 00 -	00 ·	- 250) –	143	-	00	- 00	- 001
Series	Quantities	Flip Mechanism Type	Mapping Sensor	Z-ax Motio Rang	n	Arm Length		End Effector	Fixing Method	Seria l Number
VTR	00-Single-arm	00-Upper arm flip	00-With	250m	n	143.5mm		00-Vacuum-	00-Base plate	001
	01-Dual arms	01-Lower arm flip	mapping sensor	300mi	n	176mm		suction type	mounting	002
		02-Double-armed	01-Without mapping sensor	350m	n		0	1-Gripper type	01-Upper plate mounting	003
		flip	mapping concor	400mi	n			02-Bernoulli	99-Other	
		03-No flip		450mi	n			99-Other	77-Outer	

Specifications

,	VTR —	Single-arm	Dual-arm	
VIIX		143.5mm / 176mm		
🖗 Pa	yload).5 kg	
R/W axis	Speed	36	0mm/s	
T axis		0°	°~340°	
I dxis	Speed	250°/s		
Z axis		250/300/350/400/450mm		
	Speed	250mm/s		
Appr	ox.Mass	Арр	rox. 37kg	
Cleanliness		Class1		
Repeatability		± 0.1 mm		
Rated Volta	ge and Current	Single-pha	se AC 200V 20A	

>>> The payload is the weight of the product being transferred.

Naming Convention

STR	- 00	- 03 -	00	- 48	30 -	440	- 00	- 00 -	001
Series	Quantities	Flip Mechanism Type	Mapping Sensor	Z - a Mot Rar	ion	Arm Length	End Effector	Fixing Method	Seria l Number
STR	00-Single-arm	00-Upper arm flip	00-Swept film	480	mm	440mm	00-Vacuum-	00-Base plate	001
	01-Dual-arms	03-No flip	01-Swipe-free				suction type	mounting	002
							01-Gripper type		003
							02-Bernoulli	mounting	000
								99-Other	

99-Other

Specifications

c	STR	Single-arm		
		440mm		
Þ	Payload	0.5 kg		
R/W axis	Speed	350°/s		
R/ W axis	Range of Motion	± 310° ~ ±130°		
т.	Speed	260°/s		
T axis	Range of Motion	± 165°		
	Speed	330°/s		
H axis	Range of Motion	± 165°		
7 .	Speed	550mm/s		
Z axis	Range of Motion	480mm		
Аррг	ox. Mass	45-50kg		
Cleanliness		Class 1		
Repe	eatability	± 0.1mm		
Rated Volta	age and Current	Single-phase AC 200V 20A		

>>> The rated load is the weight of the product being transferred.

www.xivitech.com



5-axis semiconductor wafer handling robot with 2 independently controllable rotary arms. It can support wafer pickup of EFEM from 2 FOUP to 3 FOUP. The robot has high precision and high rigidity.

Ports



Open Cassette

Load Port

SMIF

Optional

Solution Load Port

- DE84.
- 8" / 12" Wafers.

- Info Pad Pin and Lockout Pin.
- External I/O Interface.
- TCP/IP Communication.
- Description of the second Reader / RFID Reader.

SMIF 🔊

⋗ E84.

External I/O Interface.

- 6" / 8" Wafers.TCP/IP Communication.
- > Customizable Indicator Lights.

Customizable Indicator Lights.

Description of the second seco

Specifications

Load Port

Supported FOUPs		300mm FOUPs compliant with SEMI E47.1 and E62	
Principal Dimensions		1384(H) x 472(W) x 471(D)mm	
Weight		60 kg	
Power Supply		AC 220V±10%, 50 Hz±5%, 5A	
Communi	cation Interface	EtherCAT	
Precision	Stroke		
Precision	Repeatability	±0.05mm	
Operating	Temperature	5 – 40°C	
Environment Humidity		30 - 80%	

SMIF

Supported SMIF Pods		Interface compliant with SEMI E19.4	
Princip	al Dimensions	1384(H) x 472(W) x 479(D)mm	
Weight		50 kg	
Power Supply		DC 24V / AC 220V±10%, 50 Hz±5%, 5 A	
Commun	ication Interface	EtherCAT	
	Stroke	263mm	
Precision	Repeatability	±0.05mm	
Docking Accuracy		Center Offset <15mm	
Operating	Temperature	5 - 40°C	
Environment	Humidity	30 - 80%	

Aligner





Feature

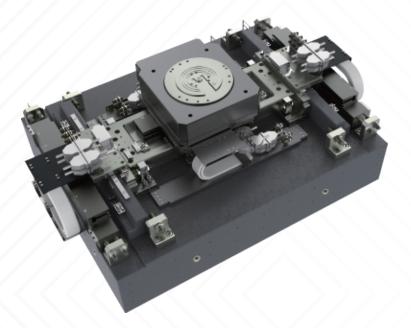
- Increasing productivity.
- > Handing of transparent glass wafers and bonded wafers.
- Notch angular accuracy, center accuracy vary depending on sensor and wafer size.
- Alignment time is the processing time at standard accuracy, and the Alignment time varies depending on the wafer size.

Specifications

WAFER SIZE		Positioning acc	Positioning	
		Notch angular accuracy	Centre accuracy	interval
	ø100 ~ ø300	±0.05° ~ ±0.1°	±0.1mm	2~6 seconds

Mechatronics Systems & Components

ABXY VMS-V VMZT Self-developed motion control components



The ABXY-ZT4 series stage is an air-bearing, mechanical motion stage with six degrees of freedom. It is specially designed for back-channel exposure machine and wafer inspection, slicing, annealing and other demanding semiconductor industry design.

Feature

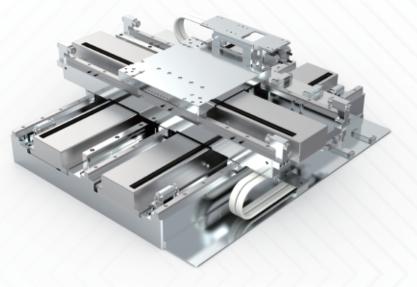
- X, Y adopts air-floating bearings, smooth operation
- T-axis: arbitrary micro-rotation for levelling
- Dual-drive stepper shaft with passive vibration damping module
- Z-axis: fast, precise focusing movement

Specifications

SPECI	FICATIONS	
	Scan Axis	350mm,500mm,
	Step Axis	350mm,500mm
Travel	Z Axis	5mm
	Tip/Tilt Axis	±2mrad
	Rz	±3°
Drive System		Linear Brushless Motor
Resolution		<1 nm
Accuracy		±200nm
Repeatability (choose linear driver)		±100nm(±50 nm Optiona
XYZ Position Stability (Air On)		20 nm
Granite Bass Thickness		250mm
Rated Payload(Maintaining Dynamic Specification	ons)	5kg
Maximum Payload		10 kg
Maximum Velocity with Rated Payload	Scan Step Axis	400 mm/s
Peak Acceleration with Rated Payload	Scan Step Axis	1G(10m/s)
RMS Acceleration with Rated Load	Scan Step Axis	0.5G(5m/s)
Stiffness,First Natural Frequency with Rated Payl	load	>100Hz
Pitch		2 arc sec
Roll		2 arc sec
Yaw		2 arc sec
XY straightness		1um
XY Flatness		1.2um
XY Orthogonality		<2 arc sec
Velocity ripple(sampled at 400mm/s)		0.1%
MTBF	/ / /	20,000 hours

Specifications

VMS-V	lower axis	upper axis			
Axis	Х	Y			
Travel	400mm	400mm			
Repeat Positioning Accuracy	±0.3μm	±0.3μm			
Maximum speed	0.35m/s	0.35m/s			
maximum acceleration	0.4g	0.4g			
horizontal straightness	±1µm	±2µm			
vertical straightness	±2µm	±2µm			
pitch angle	8arcsec	8arcsec			
angle of drift	8arcsec	8arcsec			
Minimum step	10nm	10nm			
loads	25	ikg			
orthogonality	< ±2arcse	ec XY Axis			
environments	-5 Vacuum 5×10 Pa				
convection	DC: 300nT AC: 20nT				
cleanness	ISO Class 6				
bleeder capacity	< 3×10	6 Pa·m³/s			



Feature

Excellent Vacuum Compatibility :

The platform is engineered and manufactured to rigorous high-vacuum standards, maintaining stable and reliable operation in vacuum environments down to 5×10 Pa, thereby ensuring a solid foundation for high-precision experiments and production.

Robust Magnetic Shielding :

A carefully designed magnetic-shielding structure effectively suppresses external field interference, reducing in-plane magnetic flux density to minimal levels and creating an ideal low-field environment for precision processing and testing.

Exceptional Dynamic Performance :

Structural optimizations deliver a lightweight yet rigid platform, combining agility with outstanding stability to achieve smooth, efficient motion under dynamic conditions.



The VMZT series stage is a mechanical motion stage with four degrees of freedom. Designed for the demanding semiconductor industry design associated with back-channel exposure machines and wafer inspection.

Specifications

SPECIFICATIONS		
	Scan Axis	400mm,550mm
Travel	Step Axis	400mm,500mm
	Z Axis	4mm
	Rz	±10°
Drive System		Linear Brushless Motor
Resolution		1nm
Accuracy		< ±2µm
Repeatability		< ±0.5µm
XYZ Position Stability		±0.1μm
Granite Bass Thickness		250mm
Rated Payload(Maintaining Dynamic Specifications)		5kg
Maximum Velocity with Rated Payload	Scan Step Axis	700 mm/s
Peak Acceleration with Rated Payload	Scan Step Axis	0.7G
stiffness,First Natural Frequency with Rated Payload		>100Hz
Pitch / Yaw	X Axis	< ±3 arc sec
	Y Axis	< ±4 arc sec
Straightness / Flatness	X Axis	< ±2µm
	Y Axis	< ±2µm
	Z Axis	< ±1.5µm
XY Orthogonality		<2µm
Velocity ripple(sampled at 100mm/s)		0.25%
Work Surface - Mounting Surface Parallelism		< 5µm
MTBF		40,000 hours

Feature

- X, Y adopts high rigidity, high precision guideway, micron-level running flatness and straightness.
- ZT axis All-in-one thin and light design, support 360° rotation
- Z-axis can be kept in place

Self-developed motion control components

Mechatronics Systems & Components





Controller

Active Vibration Isolation System

As the key components of motion control products, Star Microsystems self-developed product system used in the controller, active vibration isolation system, air bearing axis and motors are all self-developed products.

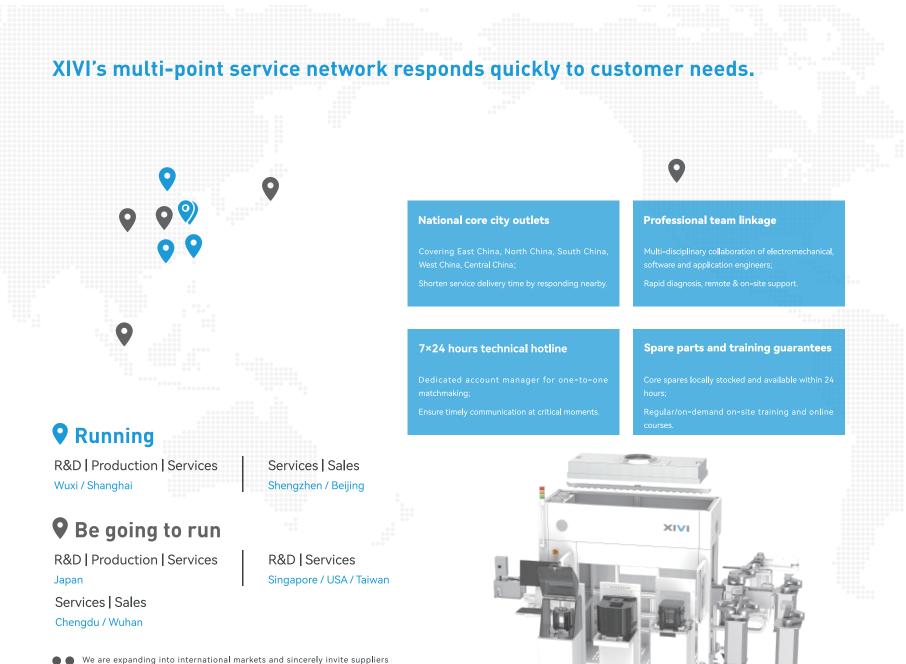
through rigorous verification tests and practical applications, these core components to ensure the accuracy, stability and reliability of the movement of our products.





Motors

Air Bearing Axis



to partner with us. If you wish to discuss cooperation, please visit our official website and contact us via our official email sales@xivitech.com



THINKER IN MOTION

ΧΙΥΙ

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